



#5/12-201 #5
STP
Pre-Amend A
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Eiji NATORI

Application No.: 09/819,687

27

Filed: March 29, 2001

Docket No.: 109121

For: METHOD AND DEVICE FOR MANUFACTURING CERAMICS,
SEMICONDUCTOR DEVICE, AND PIEZOELECTRIC DEVICE

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 35, 37, 39, 40, 45, 46, 50 and 51 as follows:

Sub C1
a1
35. (Amended) The method of fabricating ceramics as defined in claim 1,
wherein at least one of the active species and the electromagnetic wave is fed to part
of a substrate.

Sub C2
a2
37. (Amended) The method of fabricating ceramics as defined in claim 3,
wherein the first ceramic film is formed by a coating method, the liquid source
mist chemical deposition (LSMCD), the chemical vapor deposition (CVD), or a sputtering
method.

Sub C3
a3
39. (Amended) The method of fabricating ceramics as defined in claim 1,
wherein the ceramic film or the second ceramic film is formed of ferroelectrics.

40. (Amended) The method of fabricating ceramics as defined in claim 1,
wherein the ceramic film or the second ceramic film is formed at a temperature of
less than 600°C.